a component made of glass, which is transparent to said electromagnetic wave and is used for introducing said electromagnetic wave into a chamber in which said plasma is generated,

a cover component including a plurality of openings, into which said glass component is fitted, and an antenna fixed to said cover component, wherein

said glass comprises:

a first glass phase consisting essentially of Si and O; and

a second glass phase consisting essentially of Si, Al, and O, wherein said second glass phase has 0.1-10 parts aluminum-containing oxide powder added to 100 parts quartz powder.

5. (New) The plasma processing apparatus of claim 4, wherein the second glass phase has a mass ratio of Al to Si of at least 0.01.

6. (New) The plasma processing apparatus of claim 4, wherein said second glass phase has 1-5 parts aluminum-containing oxide powder added to 100 parts quartz powder.

7. (New) The plasma processing apparatus of claim 4, wherein the quartz powder has a purity of at least 99.9%.

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IN THE DRAWINGS:

Subject to the approval of the Examiner, FIGs. 1 and 2 of the application are amended to include the legend "Prior Art." FIG. 4 is amended to delete the references 4a and 4b, as indicated in the accompanying Request for Approval of Drawing Change and the attached copy of FIGs. 1, 2, and 4.

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